

## $\mu$ -XRF and EPMA An interesting combination for SEM's?

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- **Motivation**
- **Capillary optics for X-Ray beam shaping**
- **$\mu$ -XRF in a SEM**
- **Benefits and applications (sensitivity, distribution analysis, coating thickness determination, sample stability)**
- **Standardless quantification for XRF**
- **Combination of quantification for EPMA and  $\mu$ -XRF**

### Motivation

Most technical materials are inhomogeneous

=> for a complete characterisation position sensitive analytical methods are necessary

Methods for elemental analysis with good spatial resolution are known

=> EPMA, but limited sensitivity

New X-Ray optics allow the concentration of X-Rays to small spots

=> Also X-Ray fluorescence can be used for position sensitive elemental analysis

### Main features for the both methods

Method	Spotsize [ $\mu\text{m}$ ]	Element range	LOD [ $\mu\text{g/g}$ ]	Analysed Volume [ $\mu\text{m}^3$ ]
EPMA	few	C – U	1000	50 – 100
$\mu$ -XRF	down to 20	Na – U	down to 20	20.000 – 100.000

## Concentration of excitation radiation by capillary optics

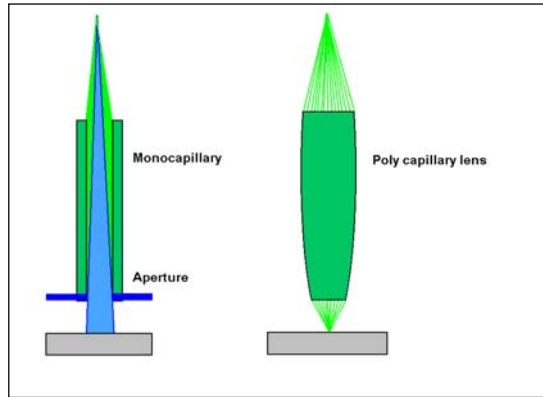
Propagation in glass capillaries due to multiple external total reflection.

In that way it is possible to shape the beam i.e. make a convergent or also a parallel beam.

So it will be possible to concentrate the excitation radiation to a small sample area.

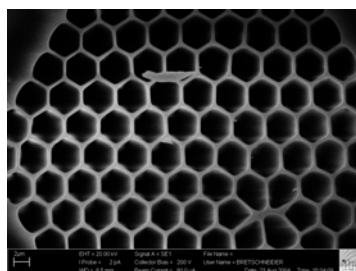
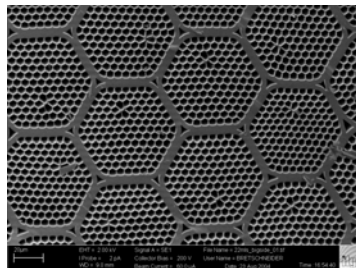
The spot size can be adapted to the special task by different optics

Intensity gain in the range of up to 5000 is possible.

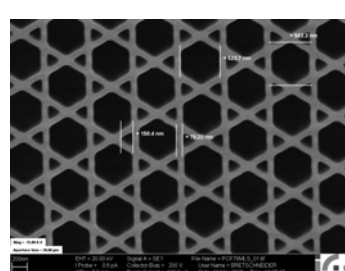
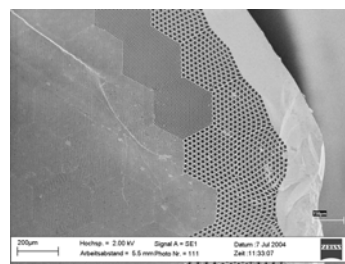


Optics	Input Ø	Transmission	Brilliance
Collimator	1 mm	100 %	1
Mono cap	300 µm	≈ 80 %	≈ 10
Poly cap	3 mm	≈ 5 – 10 %	≈ 5000

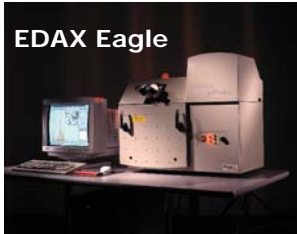
Multiple level structure of lenses



Combined structure for lenses



**Poly-capillary optics** are used already in several  $\mu$ -XRF instruments



### Motivation for the combination of $\mu$ -XRF with EPMA

The availability of X-Ray optics opens the possibility for  $\mu$ -XRF also in SEM

Then it is possible to combine electron excitation with X-Ray excitation using the same EDS-detector for measuring fluorescence of both excitation

#### Benefits:

- Higher sensitivity for trace analysis
- Enhanced information depth
- Easy sample preparation (no electrical conductivity needed)
- Low sample stress by low heating due to absorbed radiation
- Combination of quantification results of EPMA and XRF due to different sensitivities in dependence of atomic number



## Instrument scheme



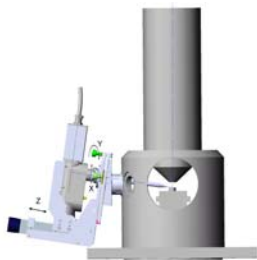
The installation is possible for every SEM.

### Requirements:

- Free port on the SEM
- Port should be opposite to the EDS-detector, geometry of 90 deg would be optimal
- Design has to be optimised for every SEM type and port

=> the length of the X-Ray optic has to be adapted

## Technical specification of the iMOXS



### X-Ray excitation :

HV:	max. 50 kV
Tube current:	max. 800 $\mu$ A
Filament heating	max. 5 A (depends on the tube)

### Electronics:

H x B x T:	165 x 376 x 420 mm <sup>3</sup>
weight:	15.4 kg

### X-Ray tube:

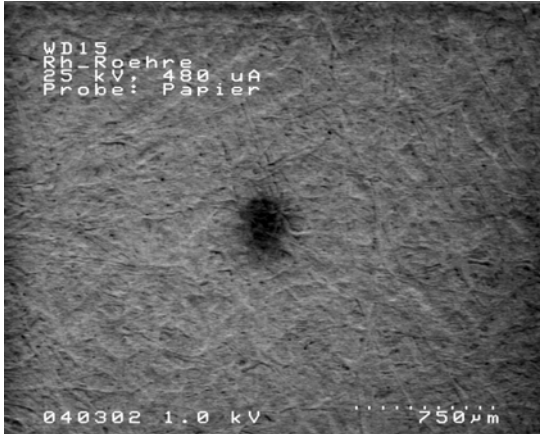
Type	Air cooled metal-ceramic tube
Anode material	Rh, W, Mo, Cu (further on request)
Anode spot	50 $\mu$ m
tube window	0.1 mm Be
Filter wheel up to 4 filter, on request	
Tube housing	with a controlled shutter
Bauartzulassung	according to German R6V

### X-Ray optics:

Mono-capillary or Poly-capillary-Lens, adapted to the SEM	
Spot size	100 – 300 $\mu$ m (mono-cap)
	30 - 100 $\mu$ m (E > 15 keV pol-cap lens)
Optic cover	with tools for alignment

**Alignment flange:** Alignment flange for adaptation to different SEM-types

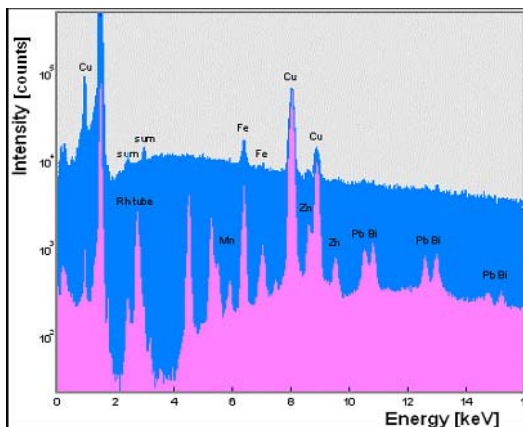
## Alignment of iMOXS



An alignment of the X-Ray spot is necessary to the position of the non-deviated electron beam

The X-Ray spot is visible by a contrast caused by charging effects on non-conductive material (paper)

## Advantage in analytical performance



### Improvement of P/B ratio

Spectra of an Al-alloy (log - scale)

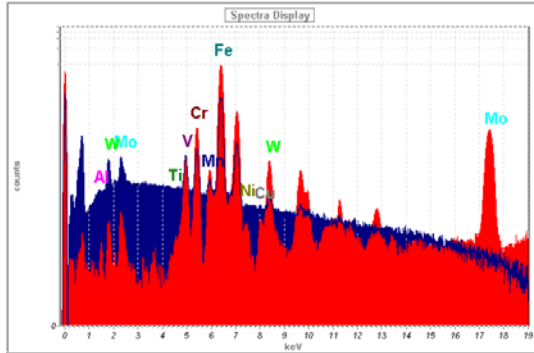
excited by electrons (blue) and by X-Rays (red)

The X-Ray excited spectrum have a significant lower background due to lack of bremsstrahlung in case of X-Ray excitation

Peaks that are overlapped by the back-ground for EPMA can be detected in case of X-Ray excitation (for example Mn, Pb, Bi)

=> Limit of detection are down to 20 ppm, that means sensitivity can be improved by a factor of **20 to 50!**

## Advantage in analytical performance



**Spectra of high alloyed steel (CRM 486)**

Excitation by electrons (blue) and X-Ray (red)

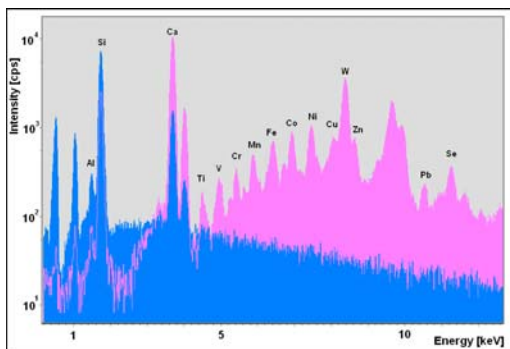
- ⇒ High intensities for main components (smaller error)
- ⇒ Undoubtedly identification of Mo
- ⇒ Identification of traces like Ni, Cu

### Comparison of typical limits of detection

Measured for different Fe- and Cu-alloys [ppm]

Elem	X-Ray	Electron
Ti	100	1000
Cr	80	800
Mn	50	800
Fe	40	800
Ni	30	900
Cu	20	1000
Zn	20	1000
Mo	200	2000
Sn	300	4000
Pb	200	5000

## Advantage in analytical performance



**Spectra of the NIST 612 (multiple element glass standard)**

excited by electrons (blue) and by X-Rays (red)

### Combination of EPMA and $\mu$ -XRF

Due to differences in excitation probability

- ⇒ Light elements are better excited with electrons
- ⇒ Heavy elements are better excited with X-Rays

For approx.  $Z = 20$  the measured intensities are comparable for both excitations

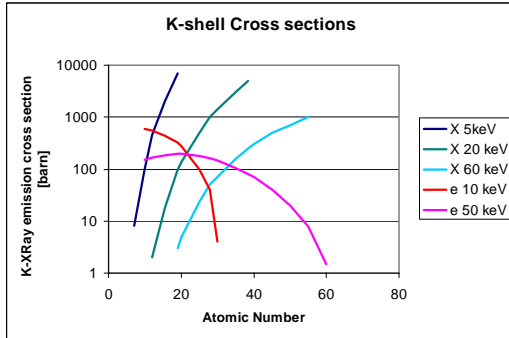
- ⇒ A combination of both quantification results should improve the overall accuracy

High sensitivity due to effective excitation and lack of spectral background

⇒ Limit of detection in the range of 10 – 30 ppm

Element	LOD
Ti	50
V	40
Cr	30
Mn	30
Fe	25
Ni	25
Cu	25
Zn	20
Pb	30
Rb	15
Sr	15

## Advantage in analytical performance



K-Shell cross sections for electron and x-ray excitation for different excitation energies and atomic numbers

Electron excitation has a larger cross section for light elements (up to 1 orders of magnitude)

X-Ray excitation is more efficient for heavy elements

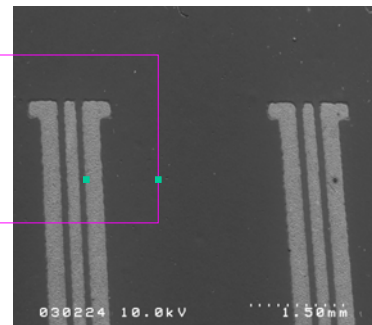
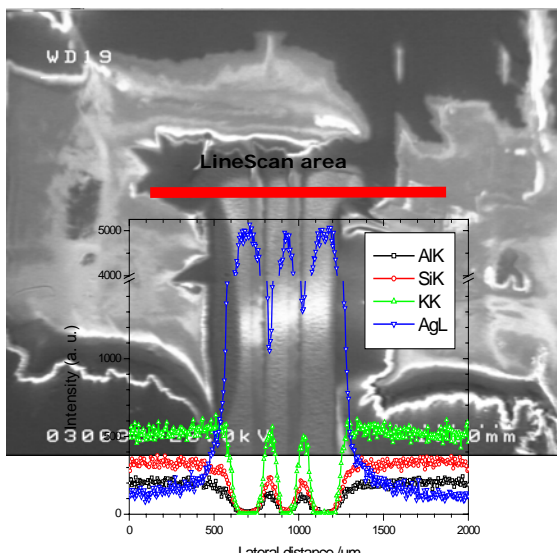
Combination of analytical results of both methods

=> improvement of analytical results due to

- two results enhance the confidence
- weighted averaging of results
- reduction of analytical errors
- iterative using of results of both excitations

=> **Improvement of accuracy of analytical results**

## Application: Multilayer ceramics substrate with Ag-circuit paths (1)

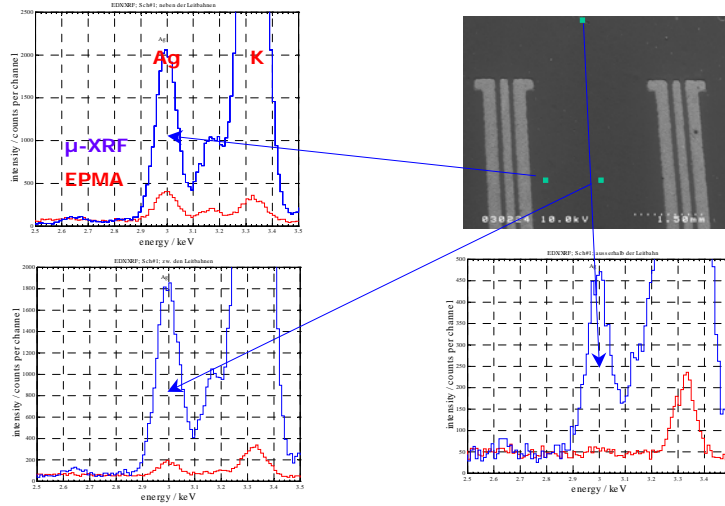


Ag seems to be present only in the tracks with EPMA. But the higher sensitivity of  $\mu$ -XRF displays Ag also in measuring points away from the track.

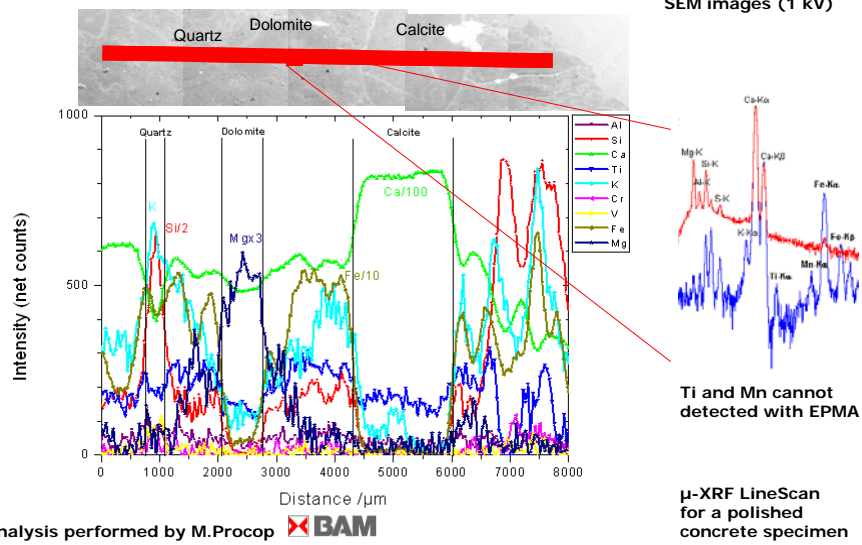
The Ag diffuses into other regions and can enhance the conductivity.

Analysis performed by M.Procop

**Application: Multilayer ceramics substrate with Ag-circuit paths (2)**

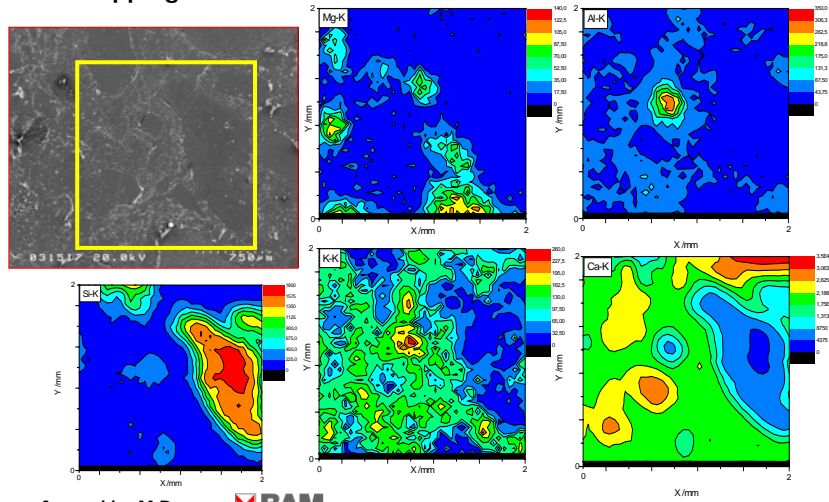


**Application: Line scan on a concrete**



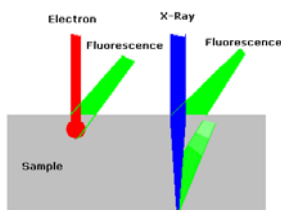
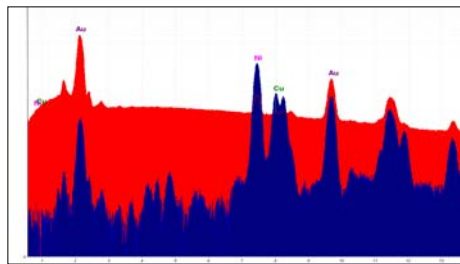
## Distribution analysis: 2D element mapping in concrete

40 x 40 Pixels a 4s, mapping via stage control



Analysis performed by M.Procop

## Advantage in analytical performance



### Enhancement of information depth

Spectra of a coating system of Au(2.0  $\mu\text{m}$ )-Ni (2.1  $\mu\text{m}$ ) on Cu excited by electrons (blue) and by X-Rays (red)

Cu can be observed only with X-Ray excitation due to deeper penetration of X-Rays into the sample

- ⇒ More representative sample characterisation for bulk samples
- ⇒ Examination of thicker layers or multiple-layer structures
- ⇒ but high sensitivity also for very thin coatings due to detector with high resolution and using low energetic radiation. Limits of detection in the sub-nm-range can be achieved

## Applications:

### Analysis of thin AuPdNi-LAYERS (1)

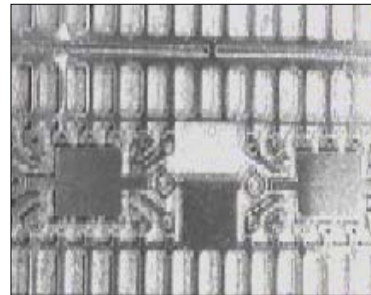
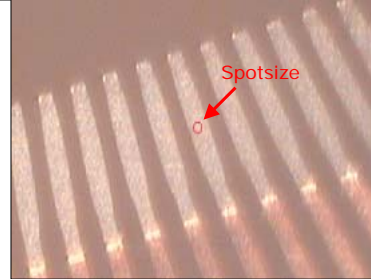
#### The Problem

LeadFrames are produced actual from Cu. The contact area only is coated with Ag. Therefore they have to be masked which needs a few additional step in manufacturing procedure. The Ag-thickness is in the range of a few  $\mu\text{m}$  and can measured with XRF.

New LeadFrames will be "over all" coated with very thin Au on Pd on a Ni diffusion layer. Typical coating thickness are 10 – 30 nm of Au and 20 – 40 nm Pd. Sometimes the coatings are also without the intermediate Pd layer. These layers are prepared by electro-galvanic or sputtering procedures

For analysis of these thin layers it is necessary to have a very sensitive spectrometer i.e. a detector with high resolution and peak-to-background ratio.

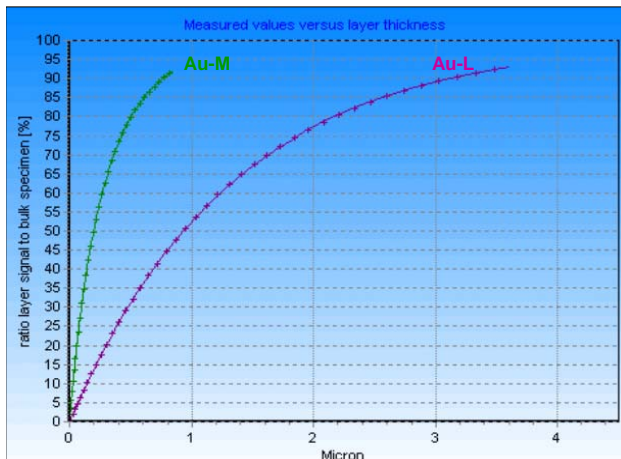
Further it can be necessary to perform these measurements on very small areas. In this case a high intensity on the sample can realised with capillary optics that concentrate the radiation on a small spot.



## Applications:

### Analysis of thin AuPdNi-LAYERS (2)

#### Self-absorption curves for Au-M and Au-L



Because of the stronger absorption of radiation with lower energies the slope for the M-radiation is higher than for the L-radiation.

That means the sensitivity for thin layers is better for the radiation with lower energy .

But than it is necessary to measure in vacuum!

The same is valid for the Pd-K and Pd-L radiation. The upper Au-coating is so thin that the absorption of Pd-L radiation is not to high.

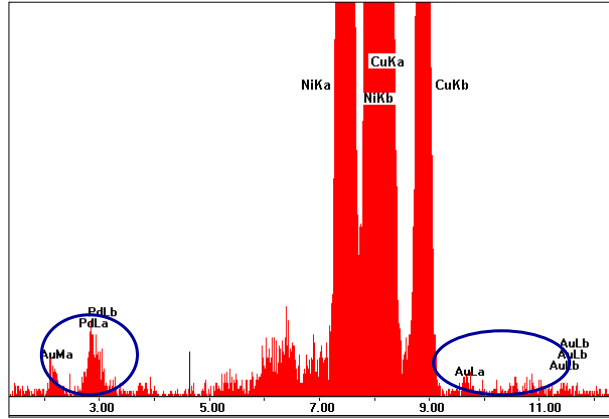
LOD for Au can be 0.1 nm for a measurement time of 300 s.

## Applications:

### Analysis of thin AuPdNi-LAYERS (3)

This very thin layers gives weak signal that can be measured only with a high resolution detector. Another difficulty is caused by the requirement to measure the weak signal on a small sample area – down to 50  $\mu\text{m}$  diameter.

This is possible only with the combination of a highly concentrated X-Ray beam (capillary optic) and a high peak-to-background ratio of the spectrometer (high resolution detector) – for example Si(Li)).



Spectrum of 16 nm Au on 36 nm Pd, Measuring time 20 s

⇒ Peak intensities very small !!

⇒ Optimising excitation and measuring conditions

## Applications:

### Analysis of thin AuPdNi-LAYERS (4)

#### Repeatability and stability (all values in nm)

Measurement		Au	Pd	Ni
Series 1 1000 x 30 s	Mean	10.96	53.3	829
	3 $\sigma$	1.08	3.6	22
Series 2 800 x 30 s	Mean	11.02	53.1	835
	3 $\sigma$	0.87	3.2	20
Series 3 1300 x 30 s	Mean	10.82	51.9	820
	3 $\sigma$	0.96	2.9	25
Average	Mean	10.93	52.76	828
	RSD	≈ 10 %	≈ 7 %	≈ 3 %
	Mean - $\sigma$	10.61	51.66	820
	Mean + $\sigma$	11.25	53.86	836

#### Conclusion

The stability (long term repeatability) of the instrument is in the range of the statistics.

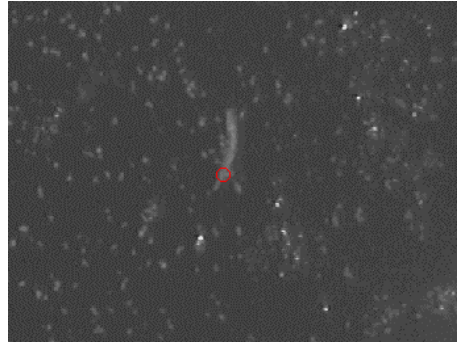
The average values of 3 repeatability measurements (over 3 different days) are within 1 sigma deviation

## Sample stability

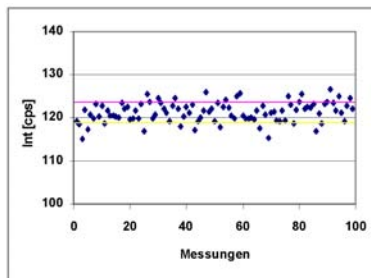
The absorption of radiation in the sample can influence the sample stability.

Prominent examples are salts. In case of electron excitation the sample size can be reduced very fast which can be observed on the SEM.

On the other hand for X-Ray excitation no changes of the sample can be observed. Therefore the intensity of S was measured for a longer period of time.



Crystallites from Ammoniasulfate  $[(NH_4)_2SO_4]$



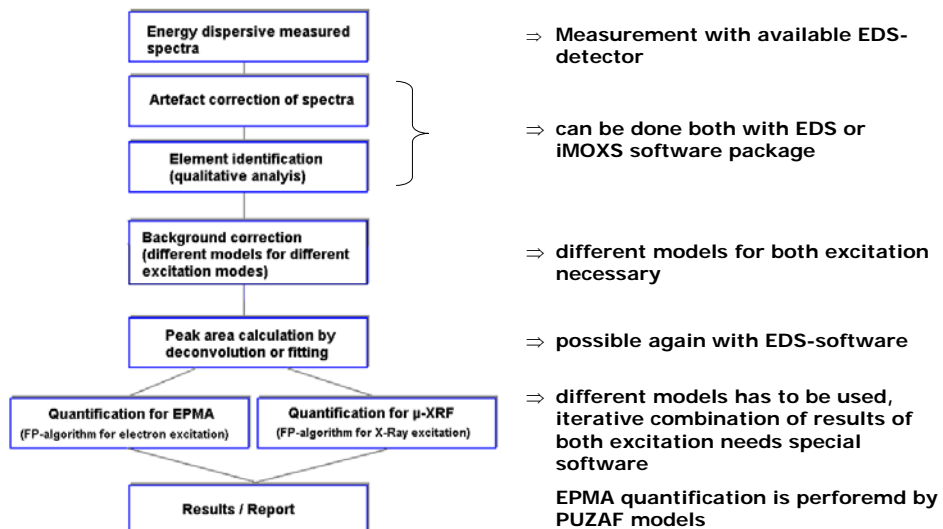
Measurement conditions:

40 kV, 200  $\mu$ A, 8 W, dead time approx. 55 %, vacuum

Measuring time: 100 x 20 s, repeated

No intensity change of a long period

## Quantification model for XRF



## Quantification model for XRF (by Tim Elam, EDAX)

$$I_i = G \cdot \int_E \frac{S-1}{S} \cdot c_i \cdot p_i \cdot \omega_i \cdot \tau_i(E) \cdot \frac{\mu(E)}{\sin \psi_{inc}} \cdot \frac{\mu(i)}{\sin \psi_{takeoff}} \cdot I_0(E) \cdot dE$$

Sherman relation

This integral will be calculated iteratively for different concentrations till calculated and measured intensities are convergent

This procedure offers the possibility

- to implement single standards to improve the rightness of the analytical result of XRF
- to implement concentrations from elements that are quantified with EPMA (light elements).

Improvement of the rightness in case of presence of light elements by their consideration either for matrix interaction and for normalisation.

Kramer, Ebel ..

Second order terms are not shown, third order terms are not considered

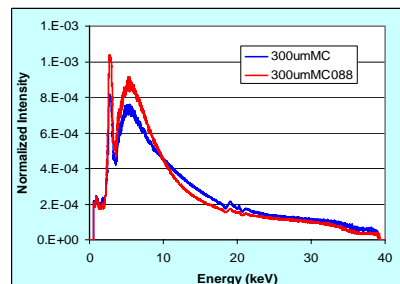
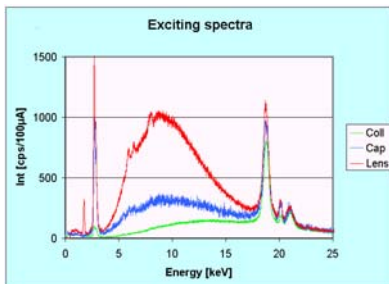
With:

- G - Geometry- and Alignment factor
- (S - 1)/S - Jump-Ratio
- $\omega$  - Fluorescence yield
- $\tau$  - Photo absorption coefficient
- p - Transitions probability
- $\mu$  - Mass absorption coefficient
- $\psi$  - Incident/Take Off angle
- $I_0(E)$  - Excitation spectrum

**Fundamental-Parameters are known**  
**Geometry factor is fitted by normalisation**  
**Excitation spectrum of the tube is influenced by the optic!!**

## Quantification model for XRF

All parameters are known in the Sherman relation. But it has to be considered that the excitation spectrum from the tube will be influenced by the capillary optic.



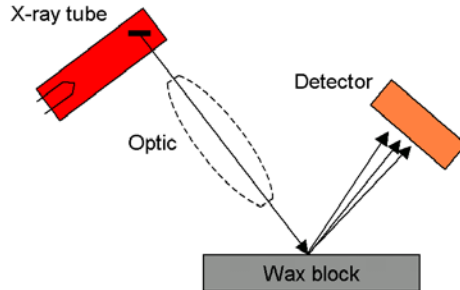
The influence of the optic depends on

- the type of the optic (Mono-cap, Poly-cap lens)
- the optic itself
- the alignment of the optic in the instrument

=> It is necessary to measure the excitation spectrum for every optic in the instrument and in the aligned position

## Quantification model for XRF

### Measurement of the excitation spectrum



In SEM's the geometry is changing for every instrument.

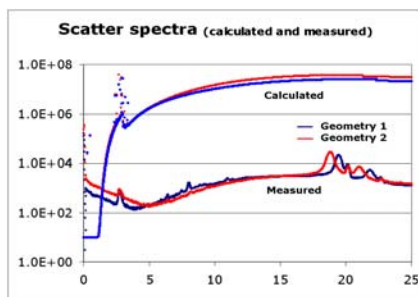
The scatter spectrum with optic can be measured in the SEM but the spectrum without optic would require every time a new adjustment.

The direct measurement of excitation spectrum is not possible in the instrument (geometrical reason, high intensity) Therefore the following procedure will be used:

- ⇒ Measurement of the scatter spectrum in the instrument both with and without X-Ray optic
- ⇒ Determination of the influence of the scatterer from measurement without optic
- ⇒ Determination of the influence of the optic from measurement with optic
- ⇒ Calculation of the transmission function of the optic

## Quantification model for XRF

### Calculation of scatter spectra



The measurement of the scatter spectrum w/o optic can not be done in the instrument.

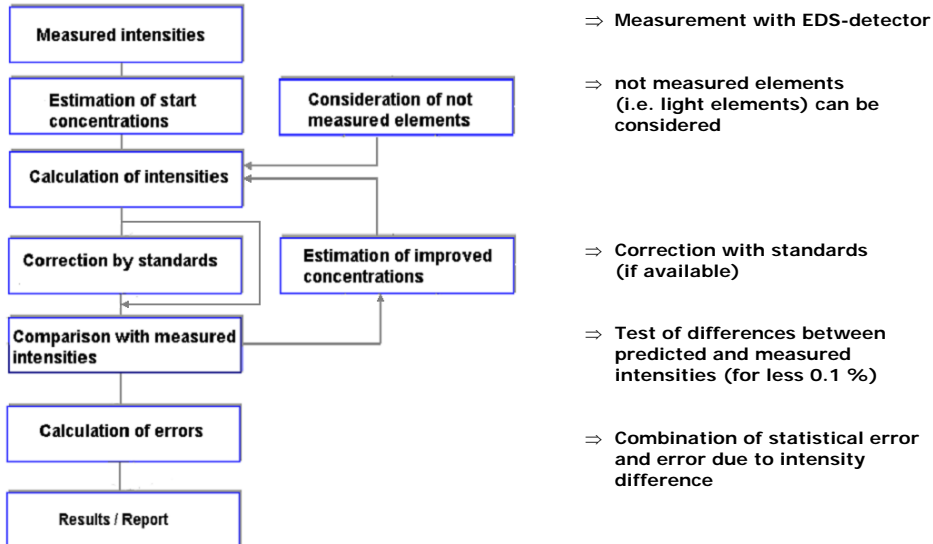
Therefore it is intended to measure the scatter spectrum w/o optic only for one geometry and transfer this to other geometries.

For that reason the scatter spectra can be calculated for different geometries. Between measured and calculated scatter spectra are still some differences caused by detector effects etc.

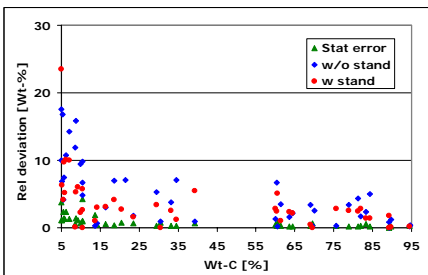
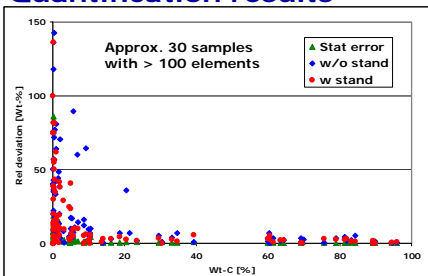
It is intended to calculate a transfer function from the calculated spectra and use this transfer function to a measured scatter spectrum for one geometry.

$$I_{scatter,Geo1} = \frac{I_{scatter,Geo1}^{calc}}{I_{scatter,Geo2}^{calc}} \cdot I_{scatter,Geo2}^{Measured}$$

## Calculation principle for quantification (by Tim Elam, EDAX)



## Quantification results



Different reference samples (steel, Cu-alloys) were analysed both wo / w one standard

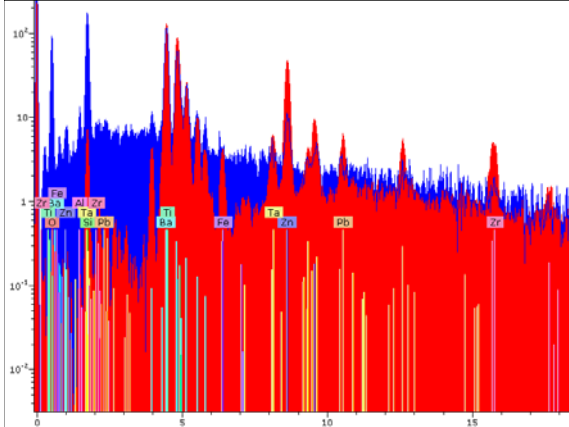
### Results:

- Consideration of the modification of excitation spectrum seems to work correctly
- Relative deviation from correct result is larger for small concentrations
- Quantification with standards improves the accuracy
- The statistical error is significantly smaller than the deviation
  - ⇒ the model, the consideration of the optic influence or fundamental parameters have to be improved

Average relative deviations for major and minor components (C > 5%)

	Major & Minor C > 5 %	Major C > 30 %
wo stand	8.9 %	2.2 %
w stand	3.2 %	1.9 %
Stat error	0.9 %	0.4 %

### Analysis of an oxid – glass



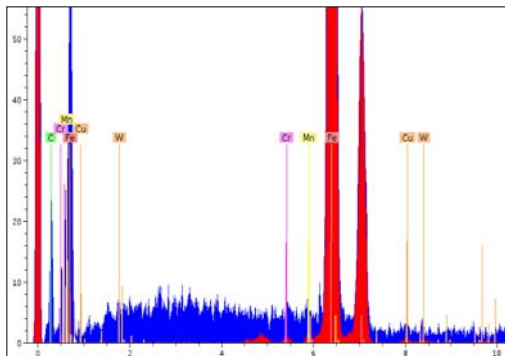
Analysis of a glass with both modes of excitation

- > light elements are better excited with electrons, traces of heavy elements cannot be detected
- > heavy elements (especially traces) are better excited with X-Rays, in general L-series of heavy elements can be used, but there is a strong overlapping
- > sensitivity in the range of  $Z \approx 20$  is comparable for both excitations

Measurement condition (comparable count rate and intensity)

Electron: 20 kV, 2 nA  
 X-Ray: 40 kV, 350  $\mu$ A

### Analysis of a low alloyed steel (with content of C)



Carbon cannot be detected with XRF but with EPMA excitation

Small concentrations of Cr, Mn, Cu and W are covered in EPMA spectrum by the background of bremsstrahlung

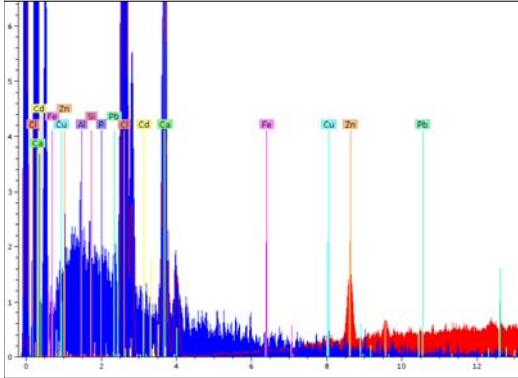
⇒ Determination of Carbon with EPMA and using this result for XRF quantification

Measurement conditions (comparable count rate and intensity)

Electron: 25 kV, 500 nA  
 X-Ray: 40 kV, 200  $\mu$ A

Elem	Given	EPMA	XRF w/o stand	XRF w stand	EPMA + XRF
C	4.98	4.51	n.d.	n.d.	4.51
Cr	0.15	n.d.	0.13	0.12	0.11
Mn	0.12	n.d.	0.33	0.21	0.21
Fe	93.49	95.49	96.70	98.30	93.87
Cu	0.28	n.d.	0.37	0.26	0.25
W	0.98	n.d.	2.47	1.11	1.06

### Analysis of a plastic sample (PVC)



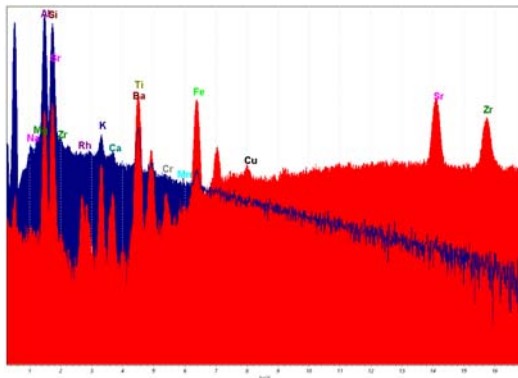
Measurement condition  
(comparable count rate and intensity)

Electron: 20 kV, 2 nA  
X-Ray: 40 kV, 350 μA

		iMOXS	EPMA	EPMA + RFA
	Given	Wt-%	Wt-%	Wt-%
C	ns	nd	62.05	62.05
O	ns	nd	17.22	17.22
Cl	ns	67.08	13.21	15.9
Ca	4.5	31.75	4.69	4.69
Fe	ns	0.04	0.57	0.003
Cu	ns	0.11	1.12	0.01
Zn	0.05	0.69	1.14	0.08

Elements that cannot be measured with XRF can be determined with EPMA. Their concentrations can be introduced into the XRF-calculation.

### Analysis of an oxid – glass K 13



Measurement condition (comparable count rate and intensity)

Electron: 20 kV, 2 nA  
X-Ray: 40 kV, 350 μA

## Analysis of an oxid – glass K458

Quantification result (Conc are given in Wt-% and error in %)

Elem	Given Wt-%	EPMA		iMOXS				EPMA + XRF Wt-%
		Wt-%	stat. error	Wt-%	stat. error	Oxide Wt-%	from oxide Wt-%	
O	56.7	55.9		nd			49.16	55.9
Mg	0.088	0.56	7.5	nd				0.56
Al	20.71	21.9	1.4	39.90	1	48.3	25.57	21.47
Si	20.19	19.2	1.5	50.70	0.9	47.4	22.16	20.10
P	0.152	0.50	7.2	0.32	60.1	0.25	0.20	0.095
K	0.42	0.42	4.5	1.40	3.3	0.55	0.46	0.402
Ca	0.095	0.08	17.2	0.29	8.0	0.13	0.09	0.081
Ti	1.11	1.17	3.6	3.79	0.6	1.96	1.18	1.030
Cr		nd		0.06	3.6	0.024	0.02	0.014
Fe	0.320	0.33	7.9	1.31	0.6	0.54	0.38	0.329
Cu		nd		0.03	3.0	0.11	0.09	0.007
Ga		nd		0.03	3.0	0.10	0.07	0.006
Sr	0.153	nd		0.81	0.5	0.261	0.22	0.191
Zr		nd		0.28	0.8	0.104	0.08	0.067
Ba	0.062	nd		1.14	2.5	0.394	0.34	0.309

EPMA + RFA:

In case of using the analytical result with better statistics and combine the quantification it is possible to improve rightness of the results.

Oxid-ratio:

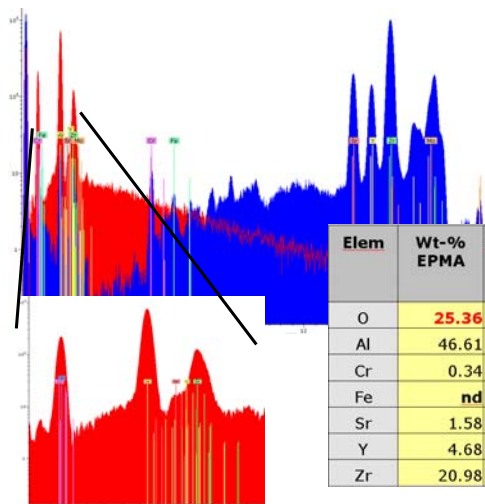
The stoichiometric relation of oxygen to the elements can be used to calculate the concentration. In this case the oxygen can take into account for the matrix interaction. From the known oxyd ratios the content of oxygen can be calculated.



Oxygen is considered here by the stoichiometric relation to the element

## Analysis of an ceramics

Quantification result (Conc are given in Wt-% and error in %)



The analysis of an ceramic (oxid) can be improved in case of combination of results of EPMA and XRF due to

- the better identification of heavy elements (Sr,Y,Zr)
- the use of results of light elements from EPMA for better matrix interaction

Elem	Wt-% EPMA	stat.error [%]	Wt-% XRF-oxid	stat.error [%]	Transfer to elem Wt-%	Wt-% ESMA+RFA
O	25.36	1.05	nd		30.71	25.36
Al	46.61	0.36	25.46	2.30	13.48	16.16
Cr	0.34	5.14	0.33	2.40	0.23	0.26
Fe	nd		0.11	3.30	0.08	0.09
Sr	1.58	2.92	6.63	0.50	5.61	5.80
Y	4.68	1.66	6.03	0.50	4.75	5.28
Zr	20.98	0.75	61.44	0.20	45.16	47.07

## Conclusion and perspectives

- Excitation with X-Rays concentrated by capillary optics in a Electron Microscope can improve the analytical performance due to higher sensitivity for traces and larger information depth
- Further for quantification the combination of results both from EPMA and XRF can enhance the rightness of analysis
- A real quantification model is used by an iterative solution of the Sherman relation. The influence of the capillary optic to the excitation spectrum is taken into account by a measurement of the scattering spectrum within the instrument. This procedure is working well and allows a good semi-quantitative analysis
- Errors of the Fundamental Parameters, excitation geometry etc. can be corrected if single standards are available. This will improve the accuracy
- For samples with a high content of very light elements like C,N,O,F it is possible to use the EPMA results within the Sherman relation. This improves the accuracy of the analytical result
- Calculation of scattering spectra would simplify the preparation for quantification. First tests was successful but have to be improved

=>  $\mu$ -XRF can be an interesting option for a SEM to improve the analytical performance and expand the range of applications